

PATENT CLAIMS:

1. Glazing comprising a glass substrate coated with a layer of aluminium oxynitride deposited by gas-phase pyrolysis, the thickness and refractive index characteristics thereof being selected so as to attenuate the reflected colours produced by an oxide layer providing the glazing with low-emission and/or solar protection properties, said layer being deposited onto the aluminium oxynitride layer.

2. Glazing according to Claim 1, wherein the constituent elements of the aluminium oxynitride layer are respectively in the following atomic proportions:

Al	from 40 to 50%
N	from 20 to 50%
O	from 10 to 60%.

3. Glazing according to Claim 2, wherein the constituent elements of the aluminium oxynitride layer are respectively in the following atomic proportions:

Al	from 45 to 50%
N	from 22 to 30%
O	from 20 to 27%.

4. Glazing according to one of the preceding claims, wherein the refractive index of the aluminium oxynitride layer is in the range of between 1.6 and 1.8.

5. Glazing according to Claim 4, wherein the refractive index of the aluminium oxynitride layer is in the range of between 1.65 and 1.75.

6. Glazing according to one of the preceding claims, wherein the thickness of the aluminium oxynitride layer has a thickness in the range of between 500 and 900 ångströms.

7. Glazing according to Claim 6, wherein the thickness of the aluminium oxynitride layer has a thickness in the range of between 650 and 850 ångströms.

8. Glazing according to one of the preceding claims, wherein the oxide layer providing the low-emission and/or solar protection properties is a layer based on doped tin oxide.

9. Glazing according to one of the preceding claims, wherein the oxide layer is a tin oxide layer containing antimony oxide, the atomic ratio Sb/Sn being in the range of between 0.02 and 0.15.

10. Glazing according to one of the preceding claims, wherein the oxide layer is a layer based on fluorine-doped tin oxide.

11. Process for the production of glazing according to one of the preceding claims, wherein the aluminium oxynitride layer is formed by pyrolysis using gaseous precursors comprising aluminium trichloride or trimethyl aluminium.

12. Process for the production of glazing according to Claim 10, wherein the gaseous precursors also comprise ammonia.

13. Process for the production of glazing according to one of Claims 11 or 12, wherein, when the aluminium precursor is aluminium chloride, the precursors also contain water vapour.

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